Supporting Information

Tungsten Oxysulphide Nanosheets for Highly Sensitive and Selective NH₃ Sensing

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S1. The density functional theory (DFT) calculations

The density functional theory (DFT) calculations were carried in the lattice structures of WS₂, tungsten oxysulphide and WO₃ to make sure the stable configurations of ammonia molecule absorption. For pure WS₂, we considered three absorption sites (Figure S5a-c), namely, on top of a W atom (T_{W1}), on top of a S atom (T_{S1}), on a hollow site (T_{h1}). ^{S1} By comparing the total energy (E_{total}) of the involved sites in Table S3, we choose the stable site T_h with the lowest E_{total} . As for tungsten oxysulphide, in the same way, we choose five absorption sites (Figure S6a-e), on a hollow site (T_{h2}), on top of a O atom with N atom absorbing (T_{O-N}), on top of a S atom (T_{S2}), on top of a W atom (T_{W2}) and on top of a O atom with H atom absorbing (T_{O-H}). The T_{O-H} site of configuration owned the lowest E_{total} (Table S4). For pure WO₃, two sites were considered, on top of a W atom with N atom absorbing (T_{W-N}), on top of a W atom with H atom absorbing (T_{W-H}). ^{S2} In the process of calculating E_{total} of two sites, T_{W-H} site of configuration is unstable, switching to T_{W-N} , so the E_{total} of T_{W-N} configuration is - 312.689 eV (Table S5).



Figure S1. (a) XRD pattern obtained from WS-2 and WS-5 using the different ratios of WCl₆ and TAA (1:2, 1:5). (b, c) Typical SEM image obtained from thin films: (b) hexagonal WO₃ nanosheets, (c) monoclinic WO₃ nanorods.



Figure S2. (a) SAED pattern of WS-10. (b) SAED pattern of WS-15. (c) SAED pattern of WS-20.



Figure S3. The dynamic sensing signals on exposure to 0.01, 0.02 and 0.04 ppm NH_3 for WS-15 at 125 °C.



Figure S4. The sensing response of the WS-15 sample toward 50 ppm NH₃ at 125 °C for 3 weeks.



Figure S5. Different sites of WS_2 configuration. (a) On top of a W atom (T_{W1}). (b) On top of a S atom (T_{S1}). (c) On a hollow site (T_{h1}).



Figure S6. Different sites of tungsten oxysulphide configuration. (a) On a hollow site (T_{h2}) . (b) On top of an O atom with N atom absorbing (T_{O-N}) . (c) On top of a S atom (T_{S2}) . (d) On top of a W atom (T_{W2}) . (e) On top of an O atom with H atom absorbing (T_{O-H}) .



Figure S7. Different sites of WO₃ configuration. (a) On top of a W atom with N atom absorbing (T_{W-N}). (b) On top of a W atom with H atom absorbing (T_{W-H}).



Figure S8. The XRD patterns of WS-13 and WS-17 (a), SEM images of (b) WS-13 and (c) WS-17.



Figure S9. XPS spectra of WS-13, WS-15 and WS-17: (a) W 4f, (b) S2p, (c) O1s, and (d) The sensing responses of WS-13, WS-15 and WS-17 to 100 ppm NH₃ at 125 °C.

As shown in the Figure S8, both the WS-13 and WS-17 samples are featured with the similar phase and nanosheet morphology as the WS-15 materials. The corresponding XPS spectra are presented in t Figure S9a-c, wherein their O/(S+O) molar ratios were calculated as 17.8% (WS-13), 10.9% (WS-15), and 13.7% (WS-15). Figure S9d further compares the sensing properties of WS-13, WS-15 and WS-17 samples to 100 ppm NH_3 at 125 °C.

W S-20.				
Material	$W 4f_{7/2} (eV)$	$W 4f_{5/2}(eV)$	S 2p _{3/2} (eV)	S 2p _{1/2} (eV)
WS-10	33.23	35.38	162.87	164.06
WS-15	32.12	34.25	161.79	162.96
WS-20	32.70	34.86	162.40	163.57

Table S1. The binding energies of W 4f and S 2p respectively from WS-10, WS-15 and WS-20.

Table S2. Comparison of NH_3 sensing performances between tungsten oxysulphide and other reported TMDs.

Sensing material	S (%)	Conc.	Lowest Conc.	Ref.
		(ppm)	detected (ppm)	
Single-layer MoSe ₂	300	300	100	[S3]
SnS ₂ /SnO ₂ composite	148	100	10	[S4]
Au doped MoS ₂	120	100	25	[S5]
Exfoliated SnS ₂	320	500	20	[S6]
TiO ₂ QDs/WS ₂	140	500	20	[S7]
PANI-WS ₂	81	200	50	[S8]
WS ₂ /WO ₃ nanohybrid	420	1000	250	[S9]
MoS ₂ thin film	120	100	10	[S10]
MoTe ₂	90	100	2	[S11]
Tungsten oxysulphide	450.23	100	0.01	This work

Table S3. The total energies (E_{total}) of WS₂ configuration system at T_{W1} , T_{S1} and T_{h1} sites.

Material	E_{total} - T_{W1} (eV)	E_{total} - T_{S1} (eV)	E_{total} - T_{h1} (eV)
WS ₂	-414.03	-413.96	-414.04

Table S4. The total energies (E_{total}) of tungsten oxysulphide configuration system at T_{h2} , T_{O-N} , T_{S2} , T_{W2} and T_{O-H} sites.

Table S5. The total energies (E_{total}) of WO₃ configuration system at T_{W-N} , and T_{W-H} sites.

Material	E_{total} - T_{W-N} (eV)	E_{total} - T_{W-H} (eV)
WO ₃	-312.689	

Table S6. The $E_{gas/sensors}$, E_{gas} , $E_{sensors}$ and E_a , of tungsten oxysulphide, WS₂ and WO₃.

Material	Egas/sensors (eV)	$E_{gas}(eV)$	E _{sensors} (eV)	E _a (eV)
WS ₂	-414.040	-19.561	-394.306	-0.172
Tungsten oxysulphide	-416.061	-19.561	-396.242	-0.258
WO ₃	-312.687	-19.561	-292.956	-0.170

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